

AMENDMENTS TO THE SPECIFICATION

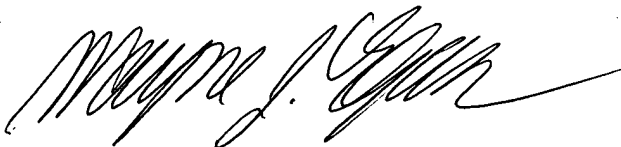
Delete the pending paragraph at page 2, lines 17-19 and replace therewith:

Anthony J. ~~Farione~~ Farino et al., "Method for photolithographic definition of recessed features on a semiconductor wafer utilizing auto-focusing alignment," U.S. Patent No. 5,783,340 (hereinafter "~~Farione~~" "Farino");

Delete the pending paragraph at page 11, lines 9-16 and replace therewith:

Referring now to Gooray '915, FIG. 1 discloses a micromechanical fluid ejector 100 fabricated using a "SUMMiT" processes or other suitable micromachining processes. As described at col. 3, lines 14-21, the SUMMiT processes are described in various U.S. patents, including the aforementioned patents ~~Farione~~ Farino, Montague, Nasby, Barron '548, Barron '788 and Rodgers. As depicted in FIG. 1 and described at col. 4, lines 35-65 the fluid drop ejector 100 comprises a movable piston structure 110, a stationary face plate 130, a fluid chamber 120 and a substrate 150.

Respectfully submitted,



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